

Figure 1a

Wet Bench: oxide etch + hydrophilic clean (RCA clean)

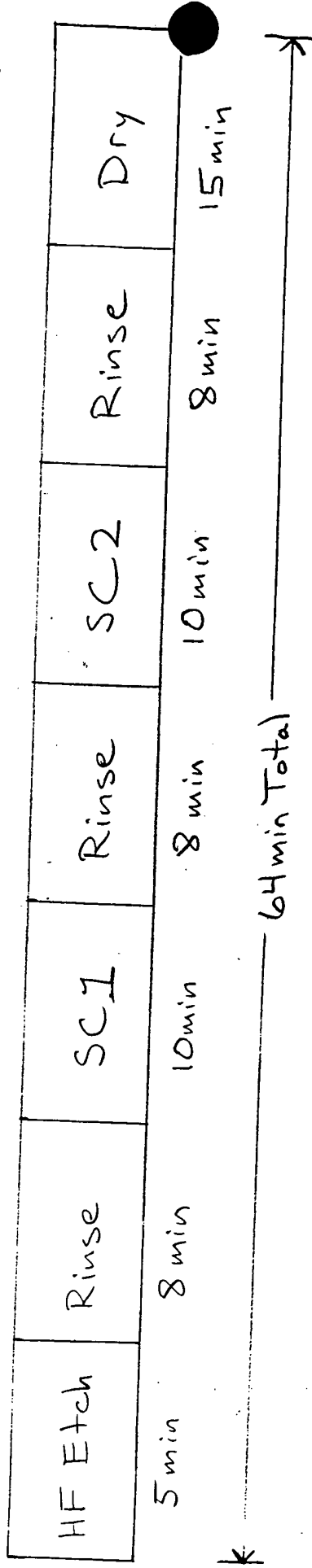
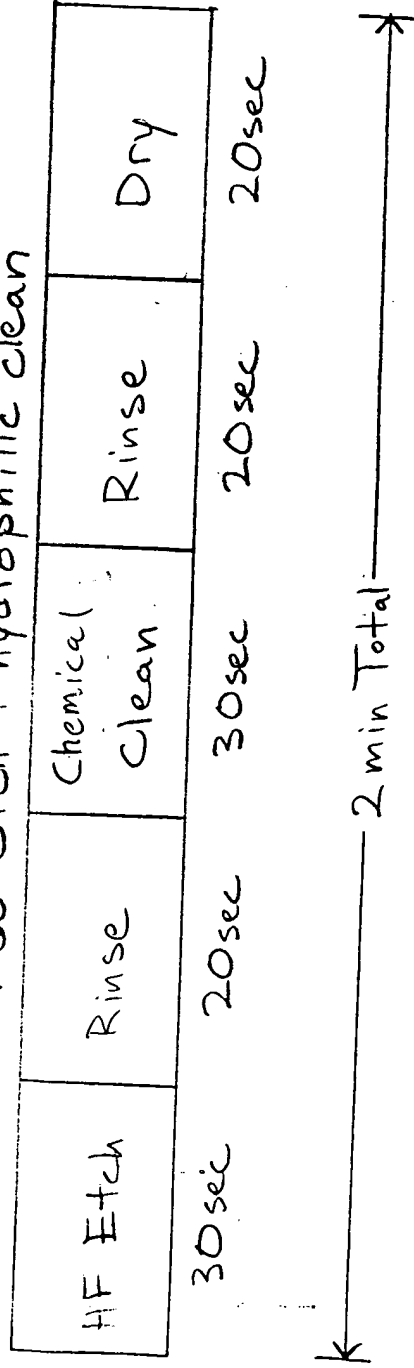


Figure 1b

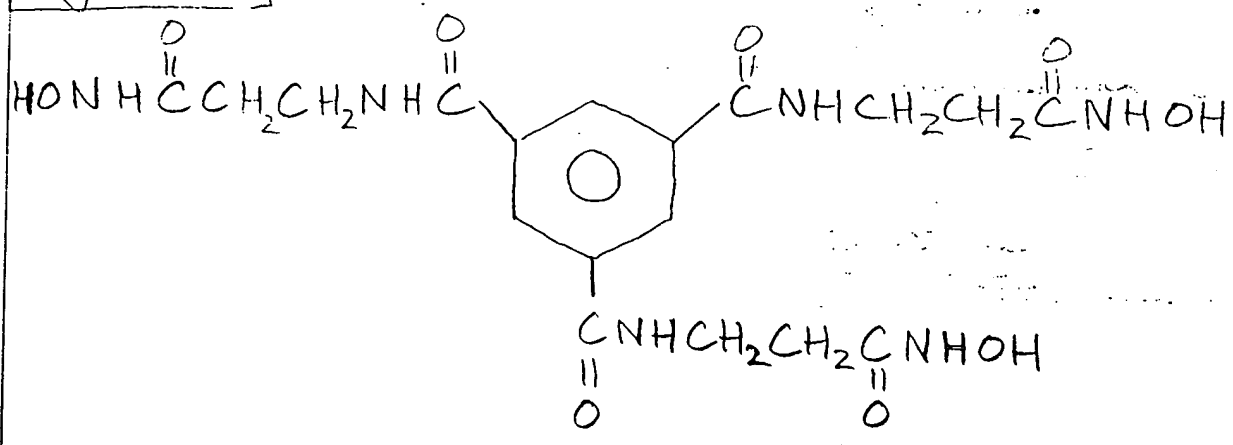
Single Wafer Cleaning Tool Single Step Clean  
oxide etch + hydrophilic clean





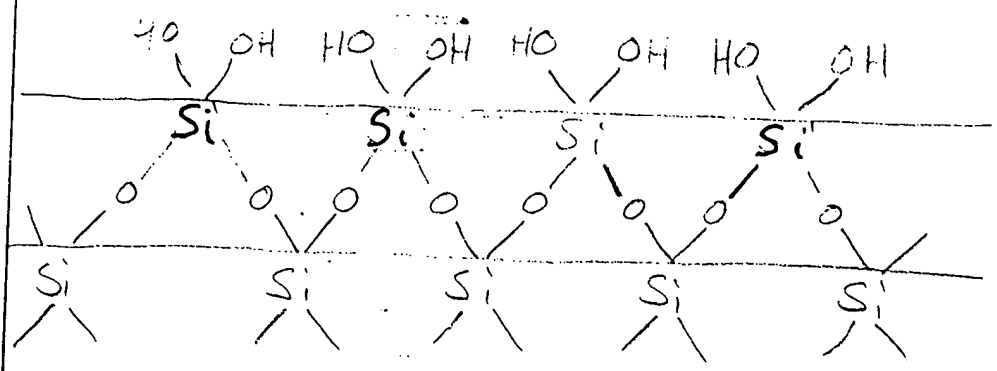


BAMFPH) Figure 3.d



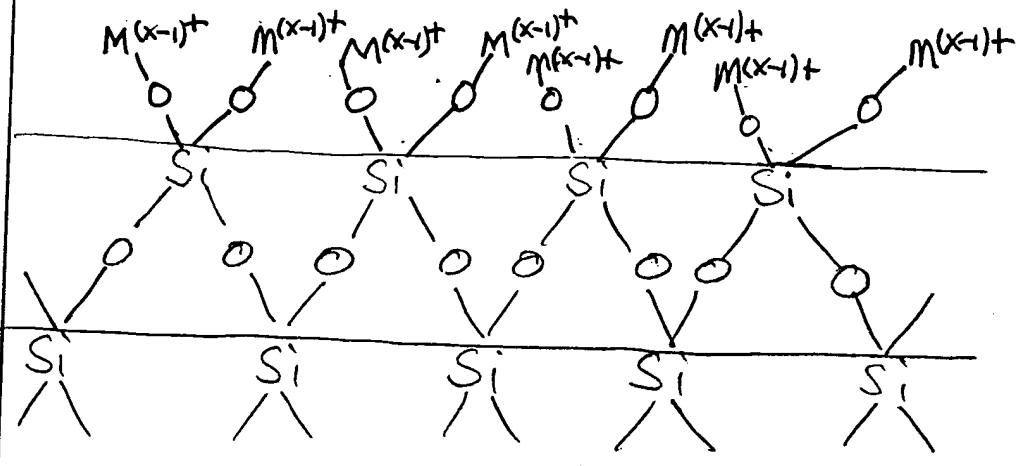
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Figure 4 a



Hydroxide terminated  $\text{SiO}_2$  film

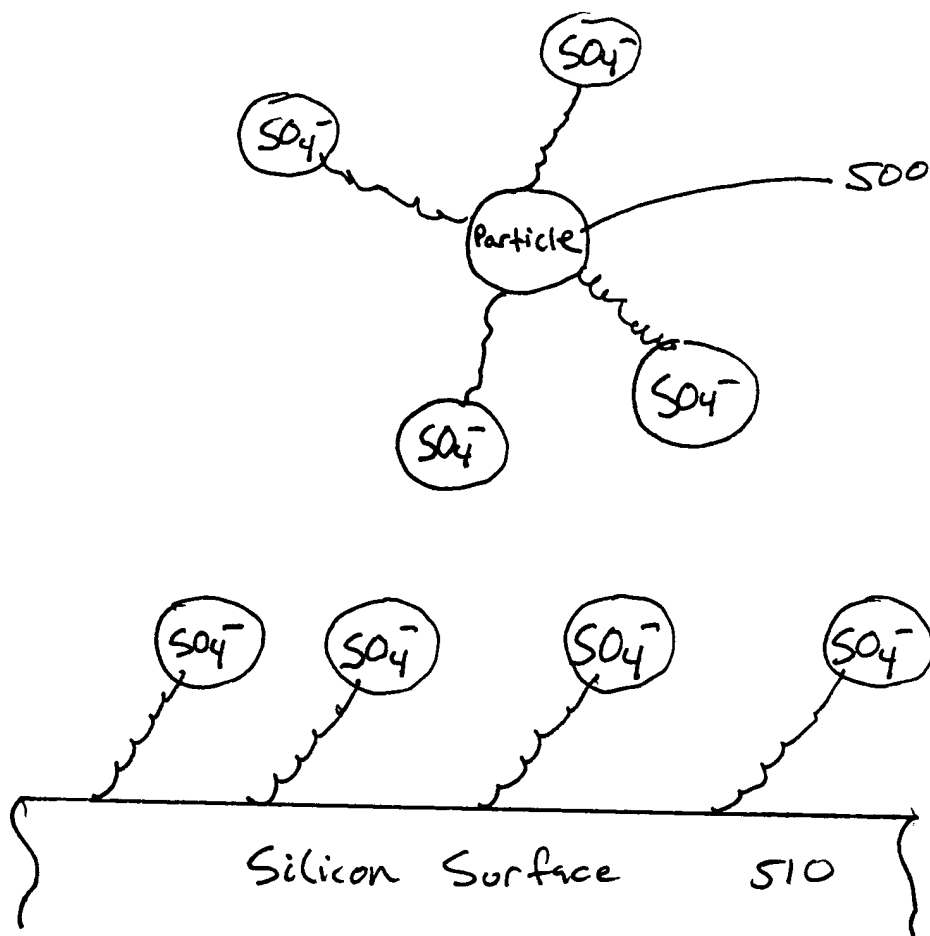
Figure 4 b



Chemisorption

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Fig. 5



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Figure 6a

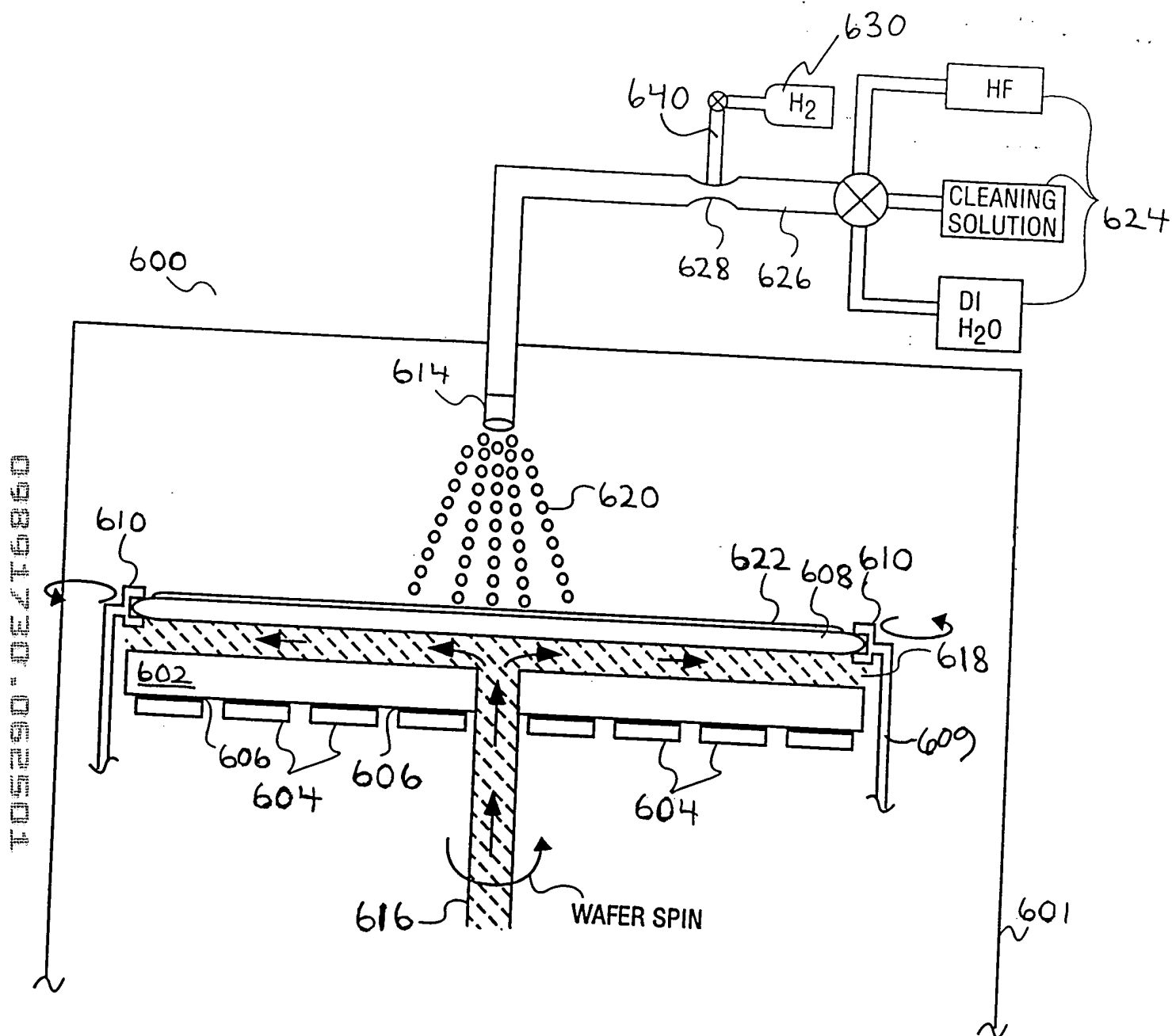


Figure 6b

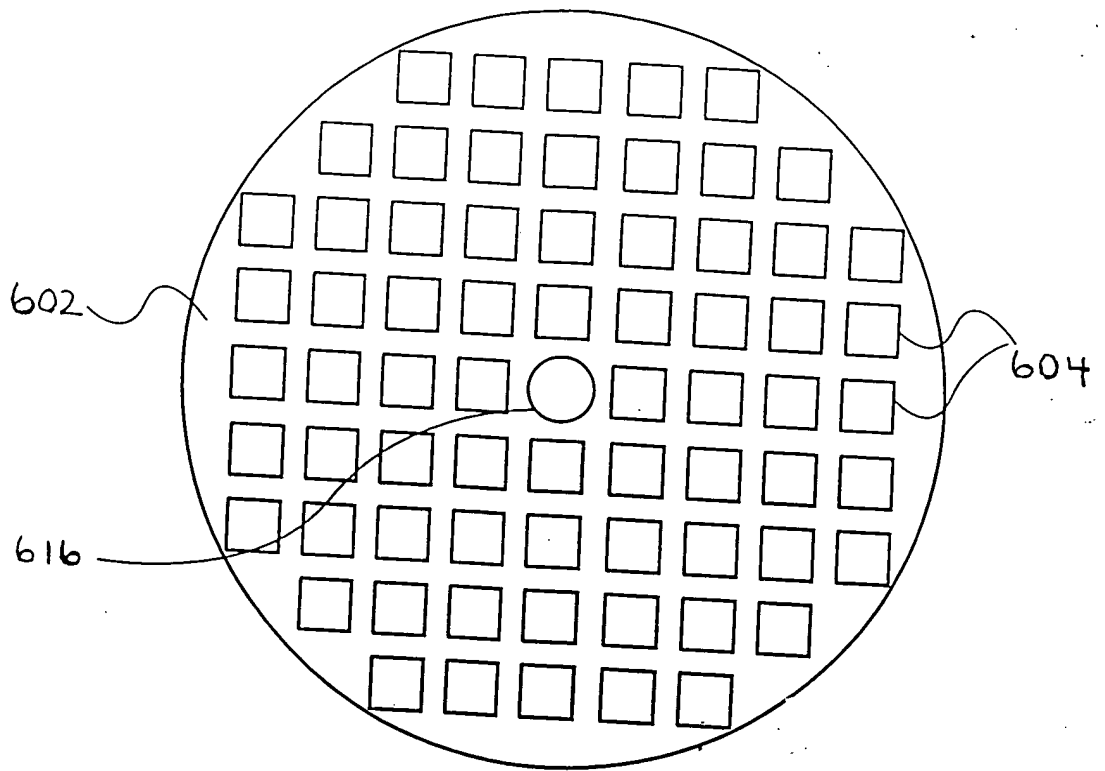


Figure 6c

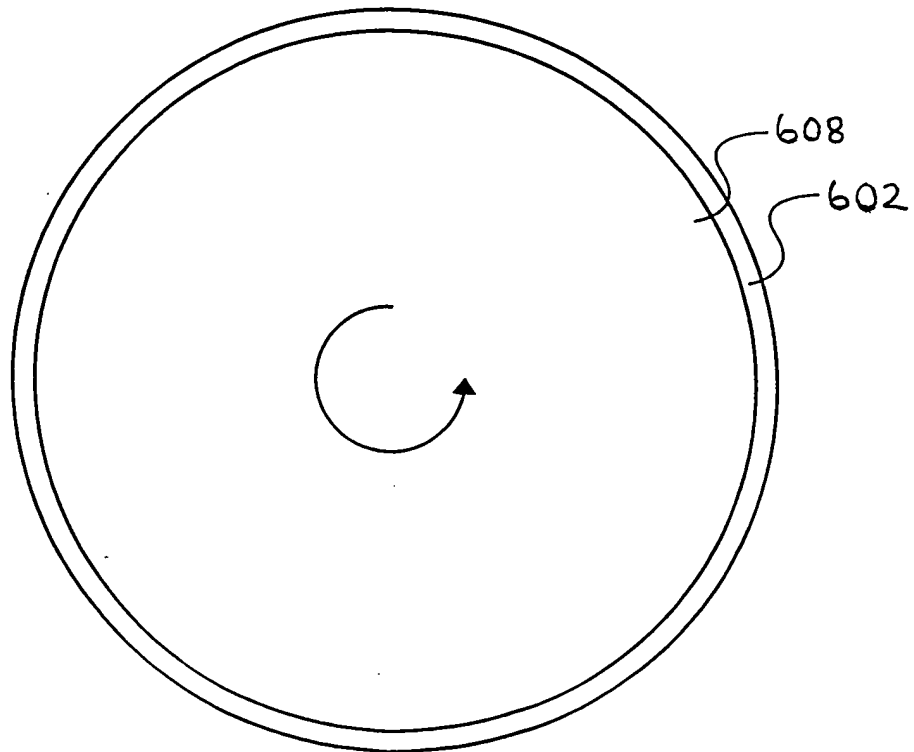
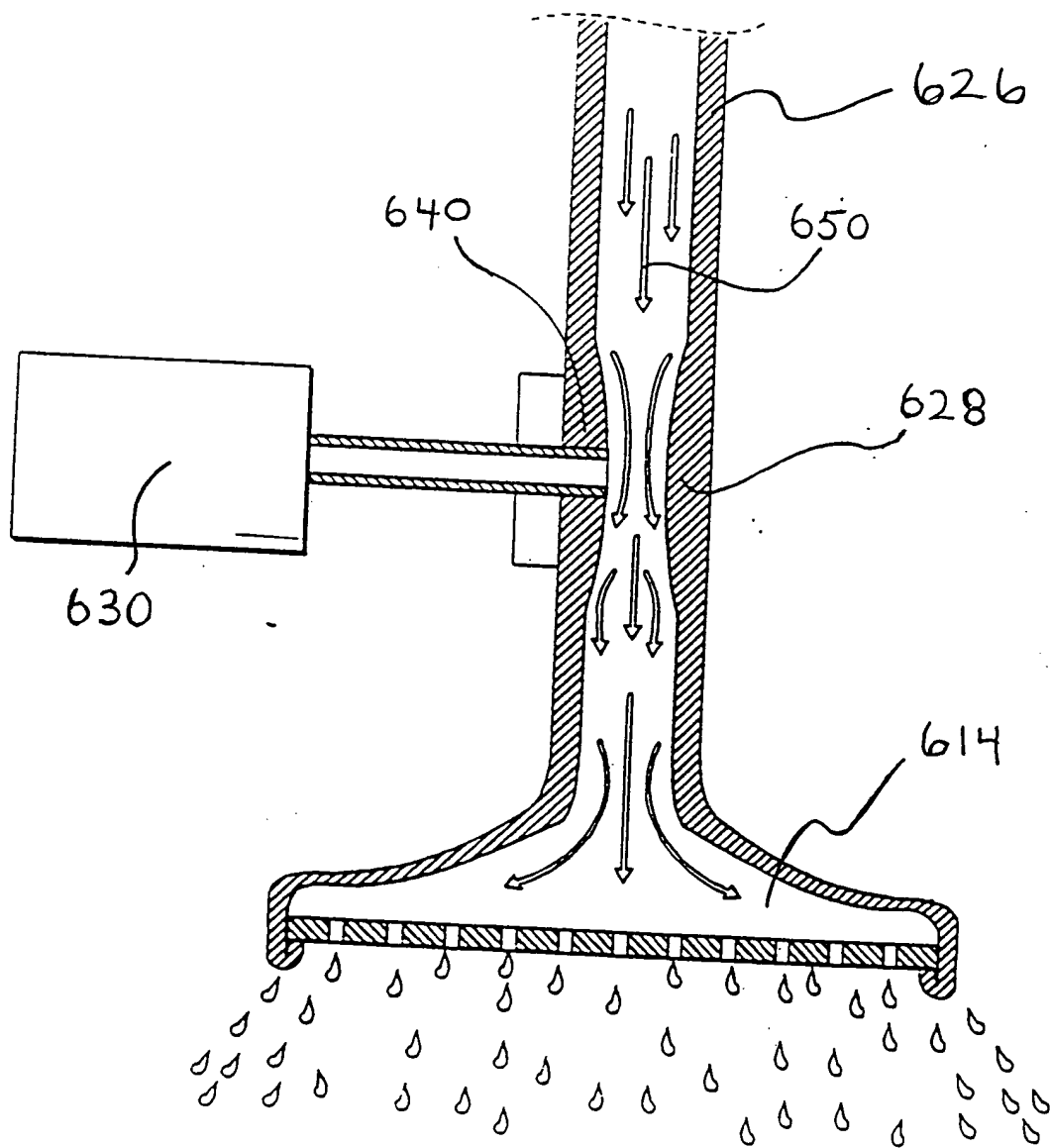


Figure 6d



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FIGURE 7

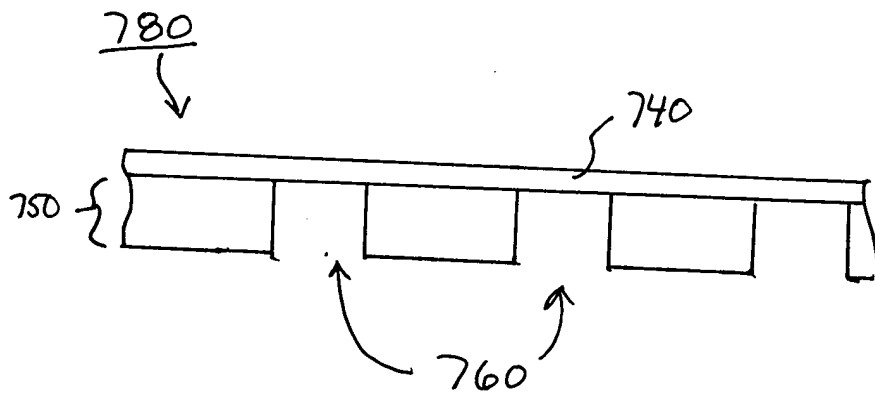
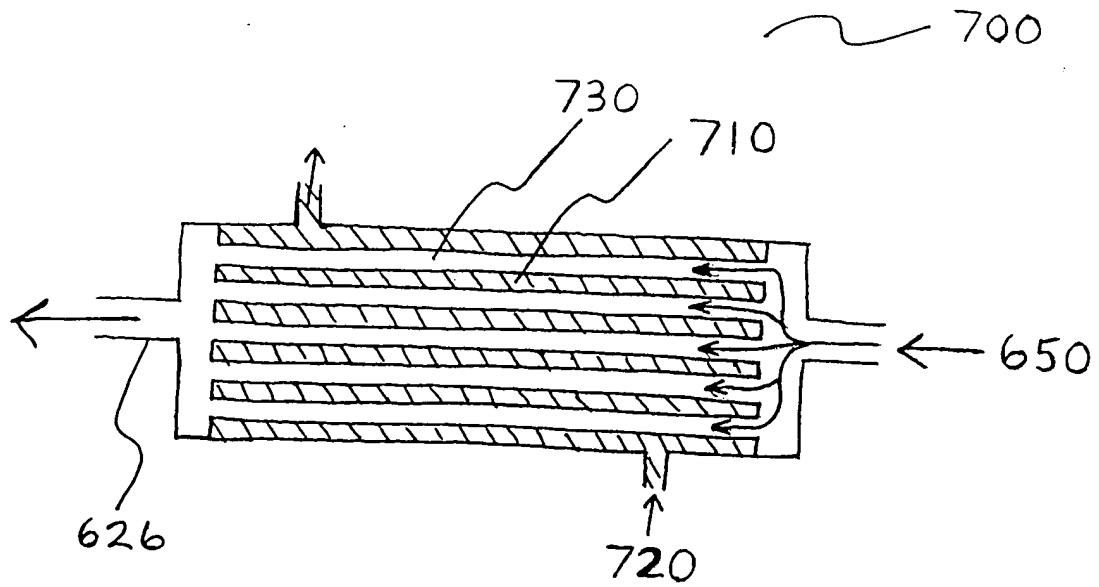


Fig. 7b

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Figure 7c

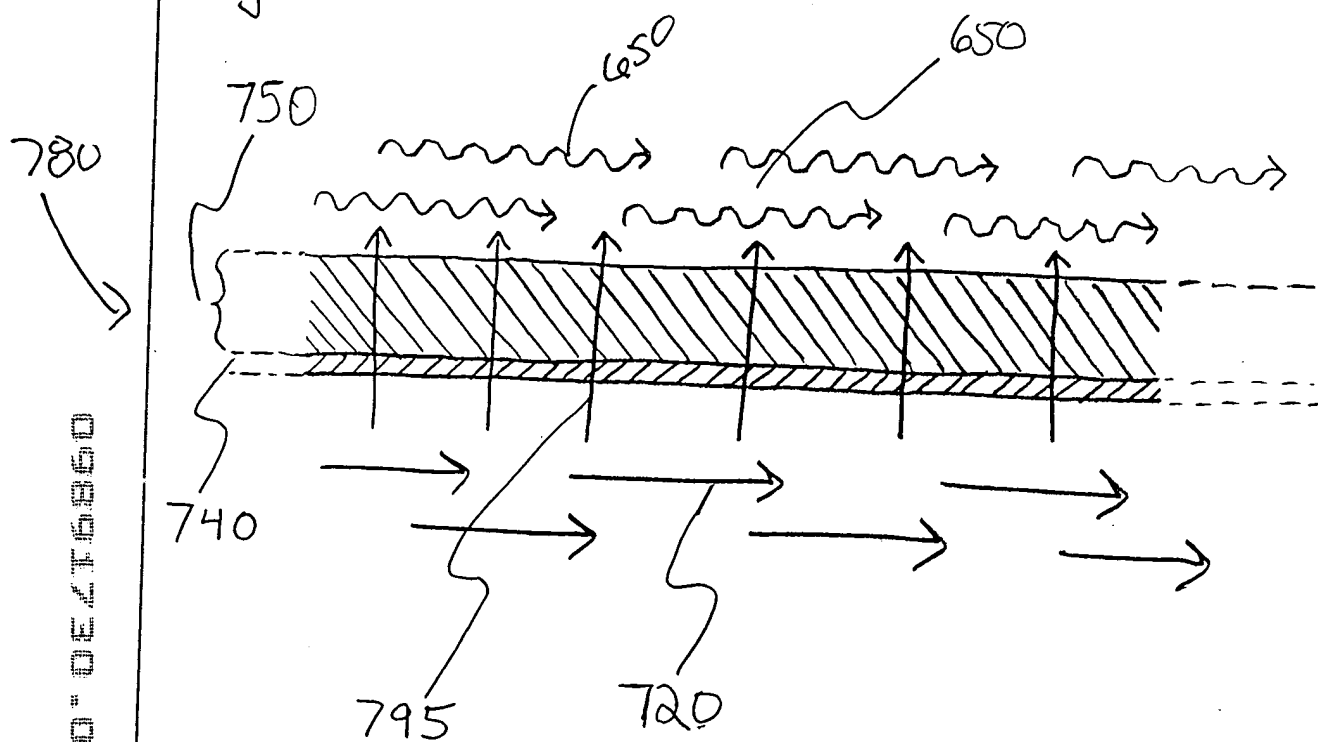
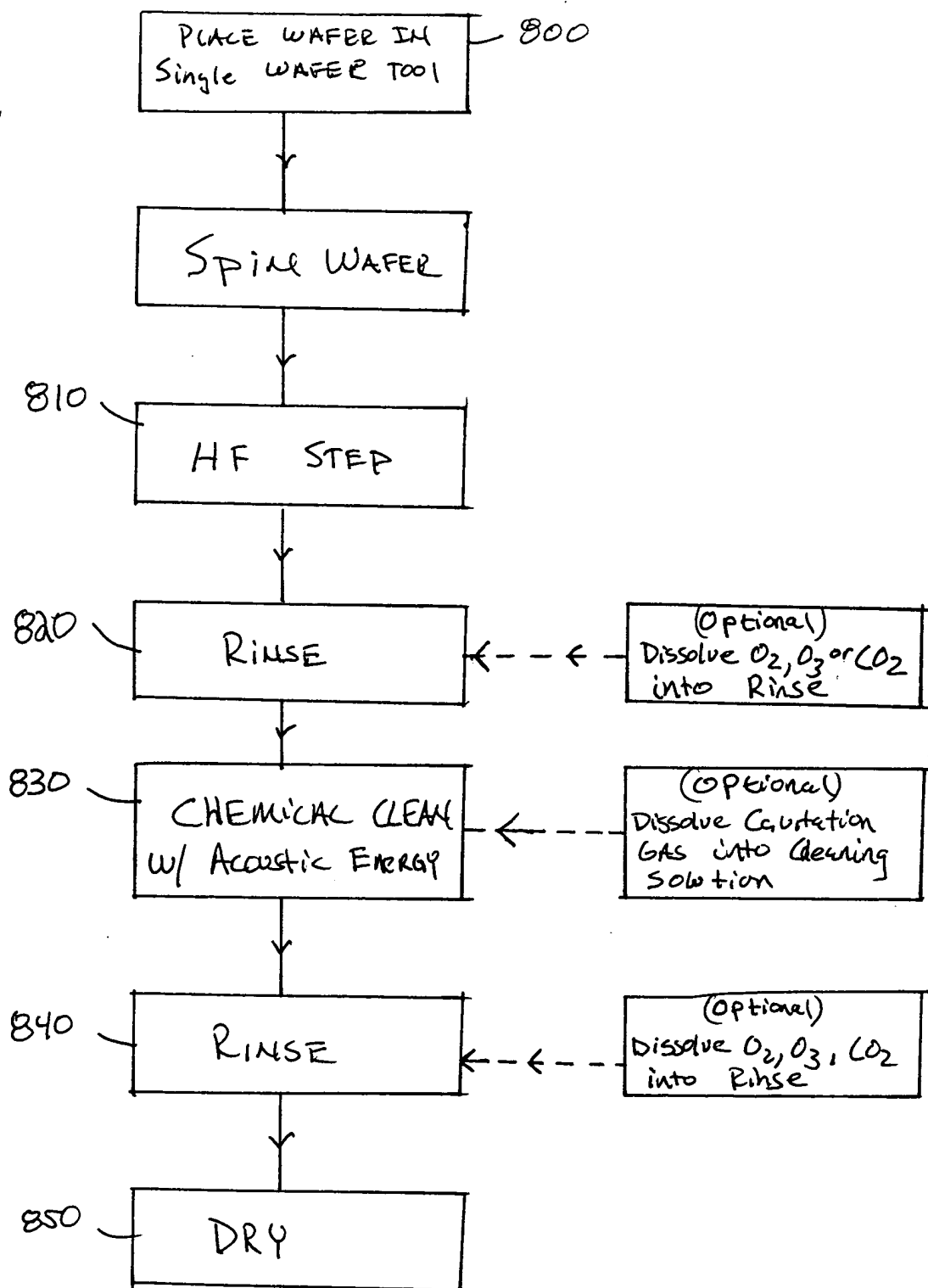


Fig. 8



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FIG. 9

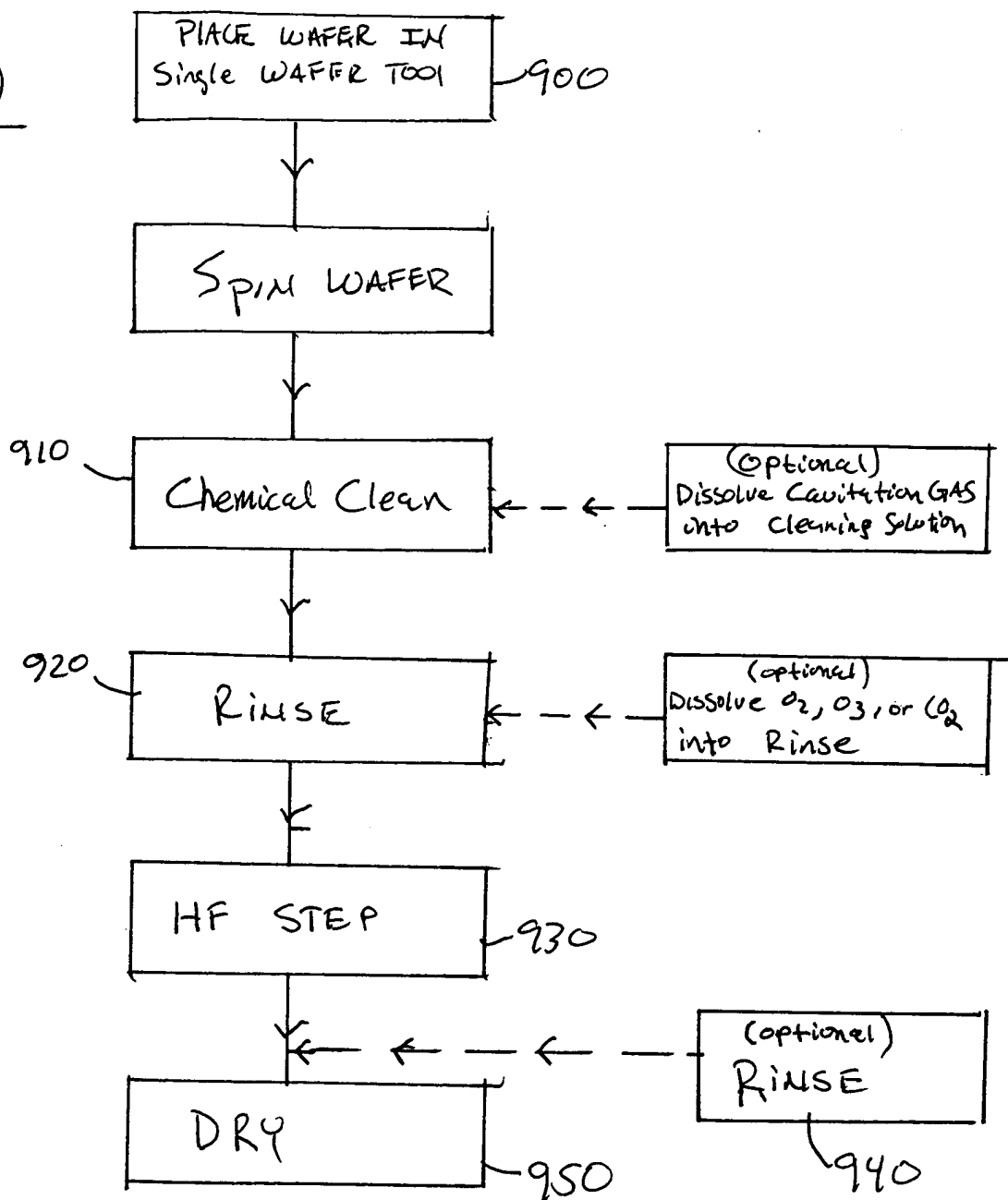


FIG. 9

HF ETCH DIAGRAM

Figure 10a

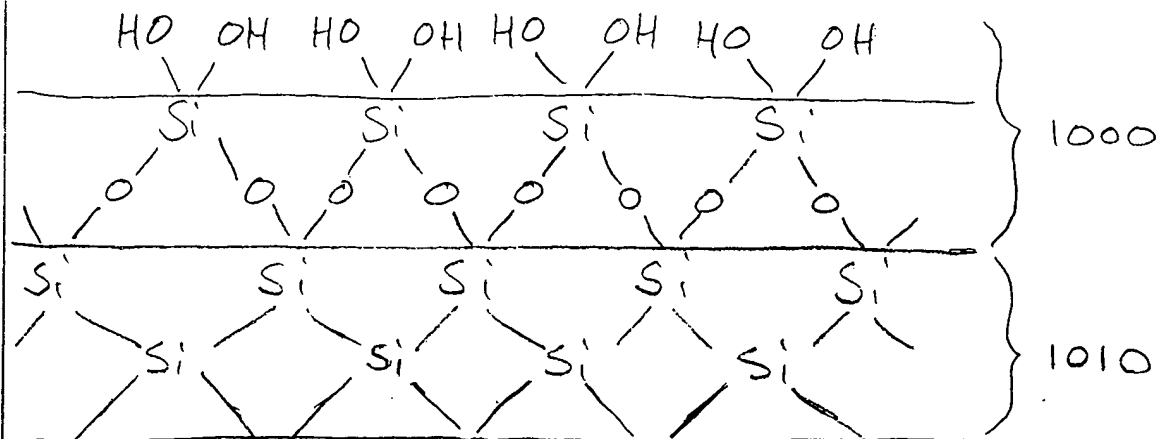
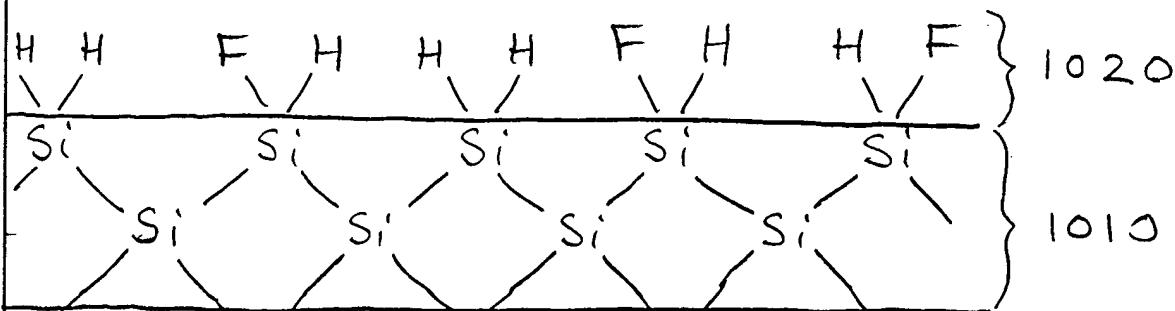
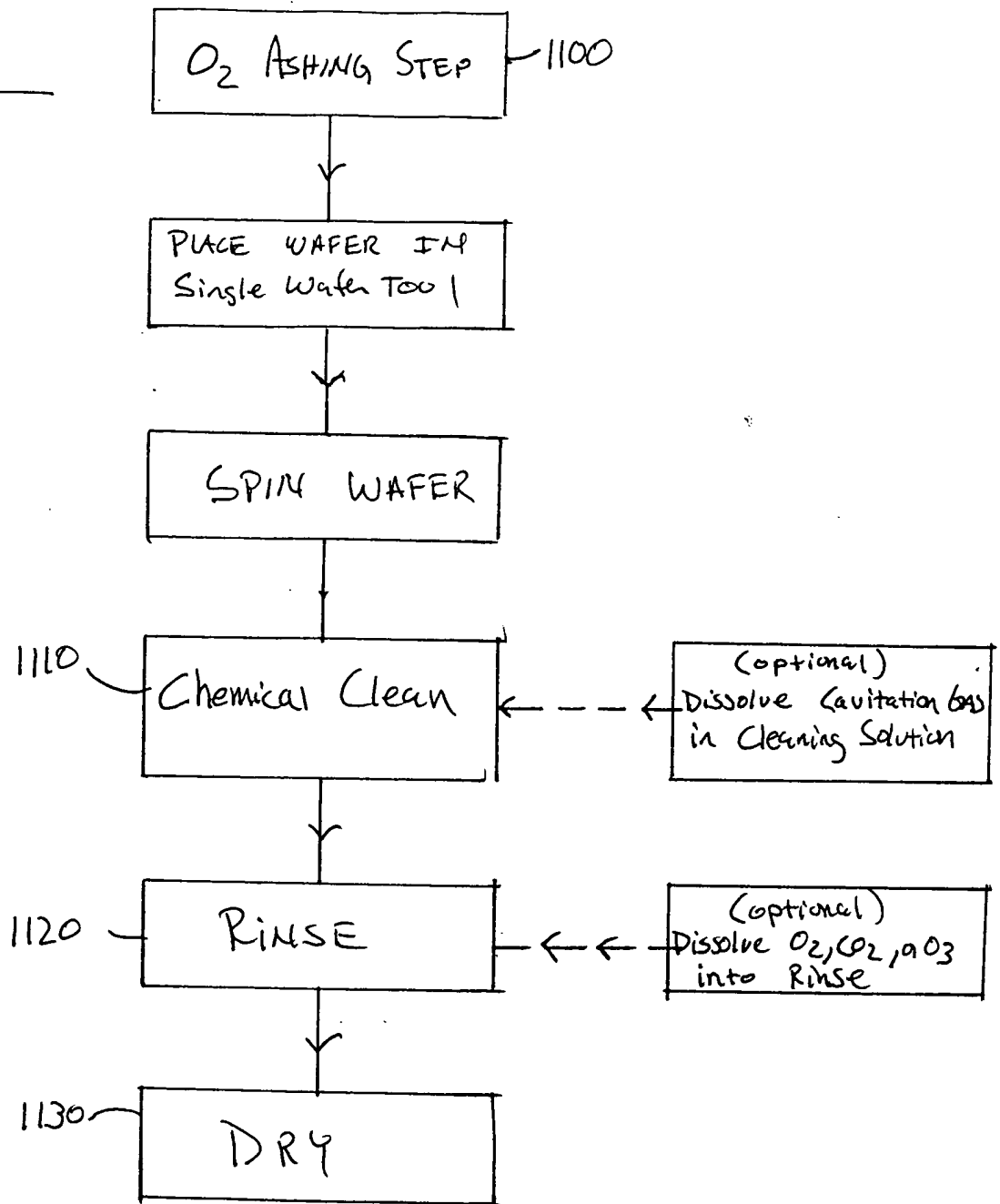


Figure 10b Hydrophobic Surface



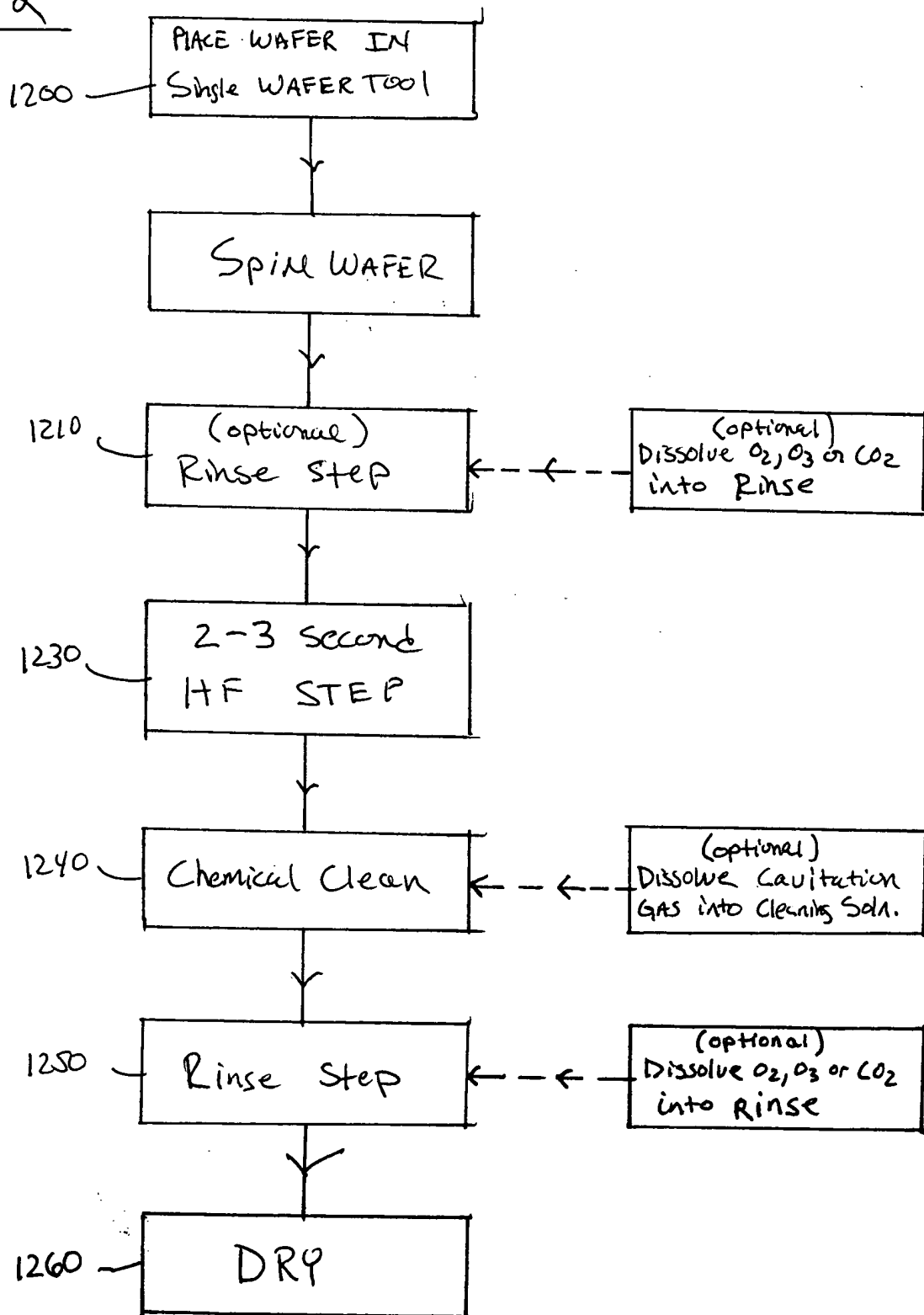
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Fig 11



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Fig. 12



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Figure 13a

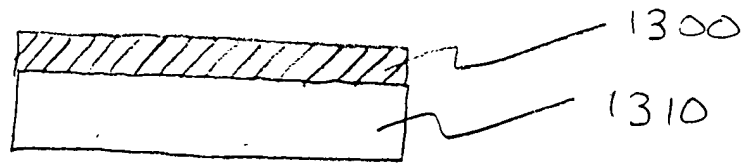
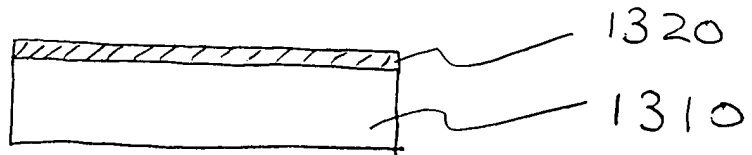


Figure 13b



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